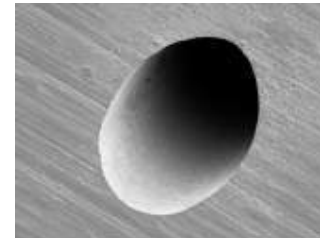
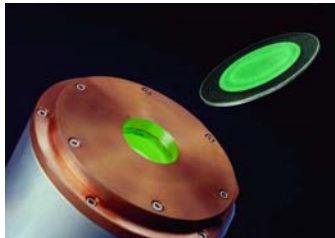




# High power picosecond lasers are ready for production



Dr. Sascha Weiler

TRUMPF Laser GmbH + Co. KG  
78713 Schramberg

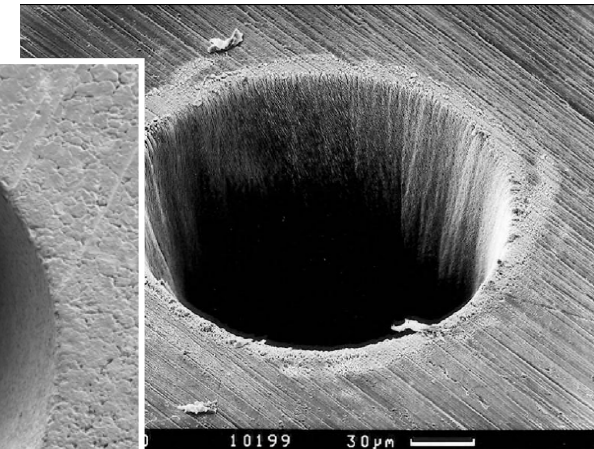
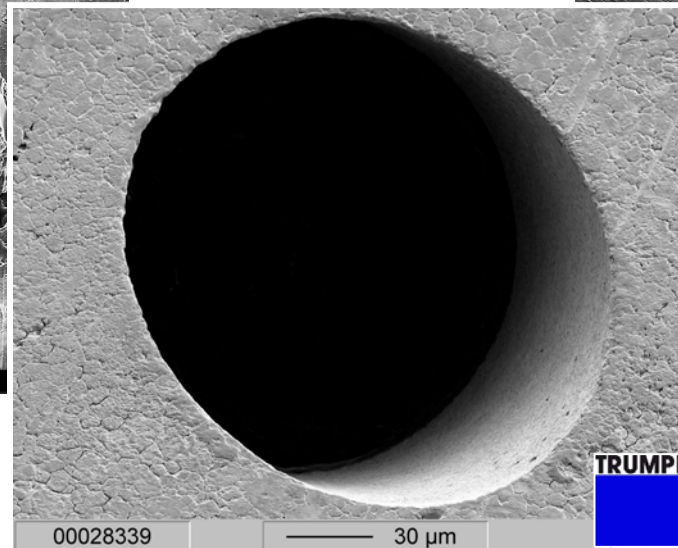
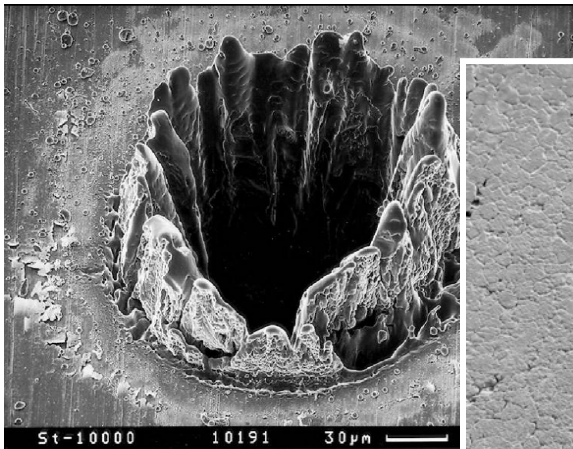


# Picosecond Lasers: fs Quality with ns Speed

ns pulses

ps pulses

fs pulses

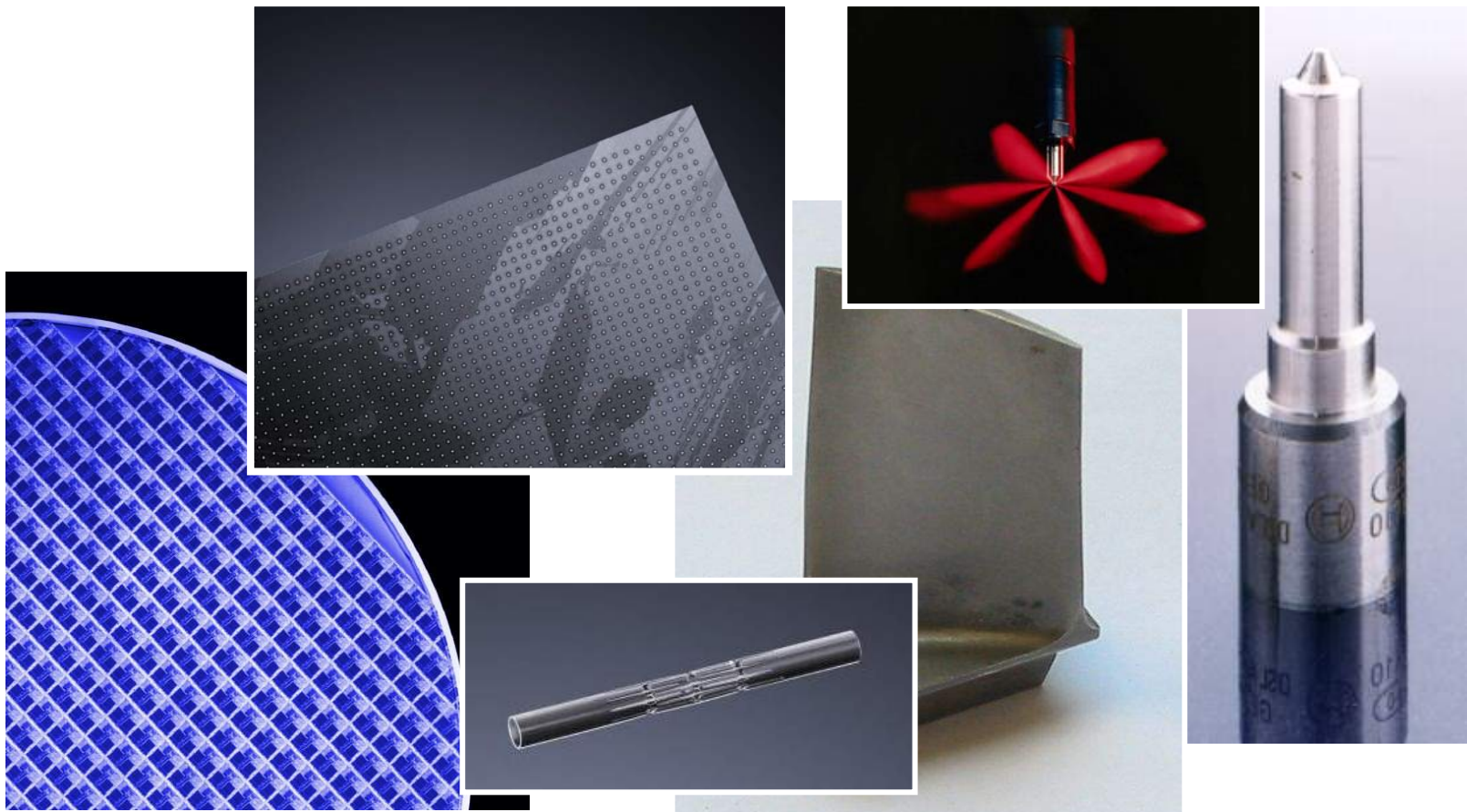


C. Momma, B.N. Chichkov, S. Nolte, F. von Alvensleben, A. Tünnermann, H. Welling, B. Wellegehausen, "Short-pulse laser ablation of solid targets", Opt. Commun. **129**, 134 (1996)





# Micromachining with Picosecond Lasers





## Drilling with picosecond pulses

- Phase 1: „Digging in“  
( $t \leq 1 \text{ ms}$ )
- Phase 2: Drilling through  
( $t = 1 \text{ ms} - 1 \text{ s}$ )
- Phase 3: Forming the Exit Side  
( $t = 0.01 - 10 \text{ s}$ )



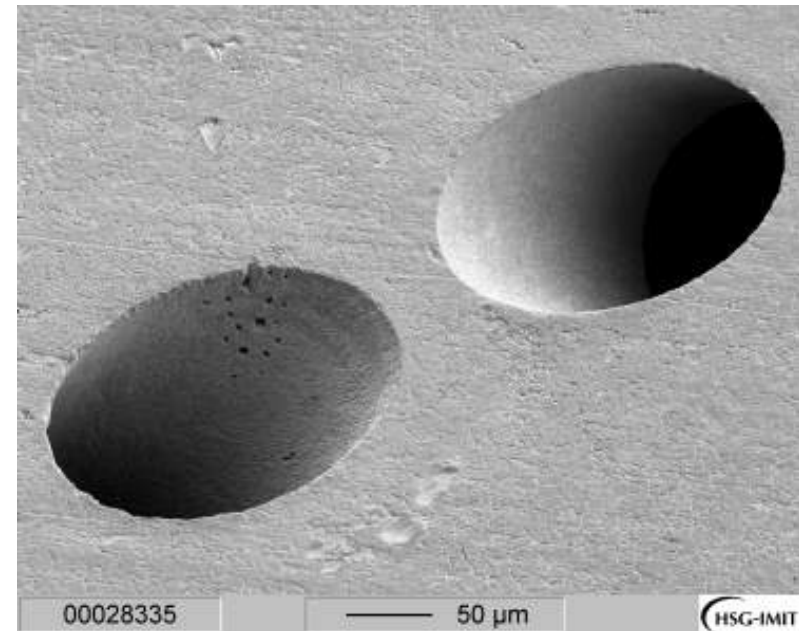




## Drilling with high Aspect Ratio

### Helical Drilling of Stainless Steel

- No melt or debris
- No Heat Affected Zone
- Free selection of taper (positive, negative or zero)
- Diameters: 50 to 100  $\mu\text{m}$
- Material thickness: up to 1.5 mm
- Applications: Injectors, cooling holes, filters

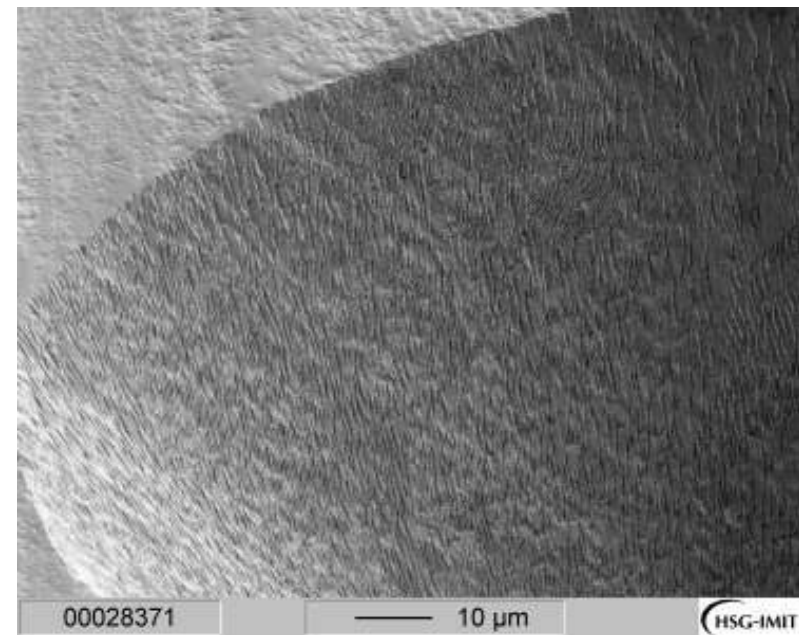




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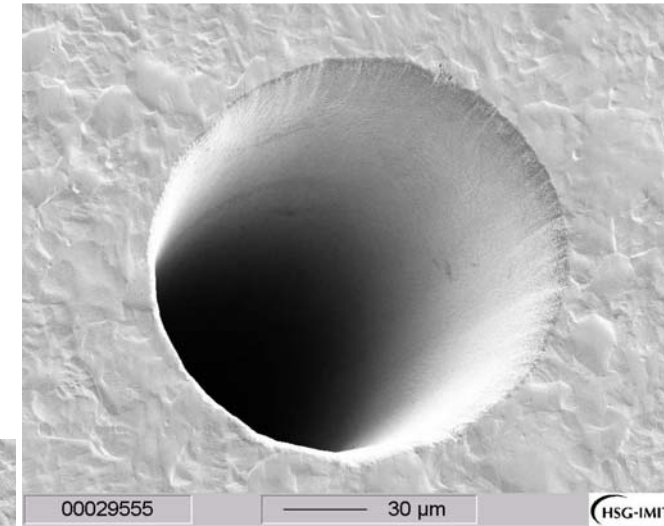




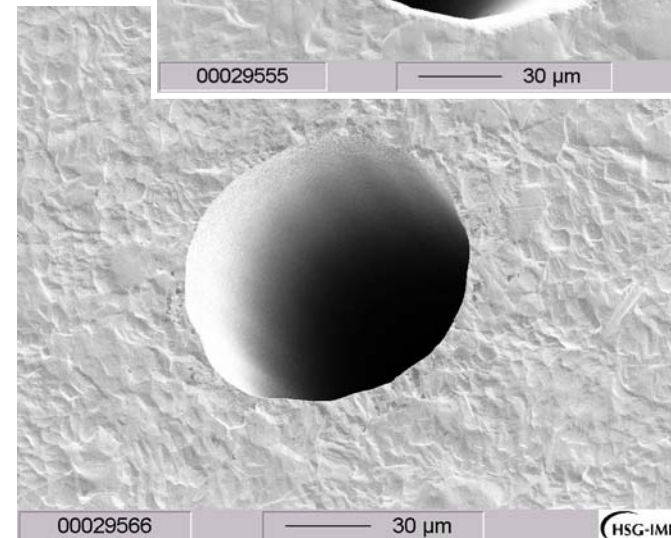
## Drilling with high Aspect Ratio

### Helical Drilling of Titanium

- No melt or debris
- No Heat Affected Zone
- Free selection of taper (positive, negative or zero)
- Diameters: 50 to 100  $\mu\text{m}$
- Material thickness: up to 2 mm
- Applications: cooling holes for turbine blades



Entrance



Exit

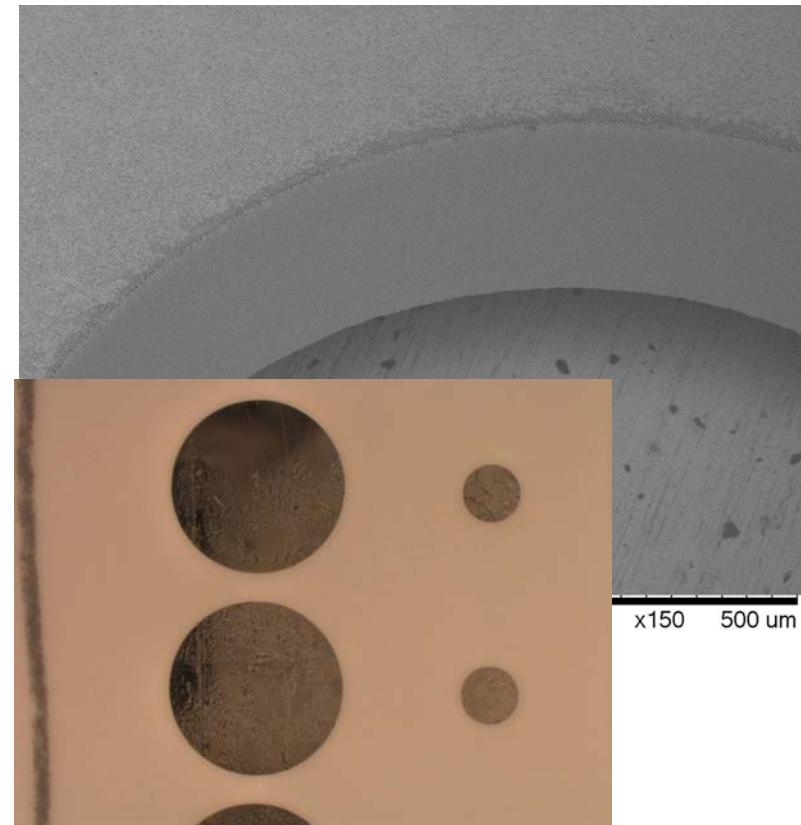




## Drilling with low Aspect Ratio

Drilling of Ceramics (AlO, AlN, etc.)

- Percussion Drilling / Trepanning with Scanner Optics
- Diameters <math>< 100 \mu\text{m}</math> – X mm
- Low HAZ
- No Chipping/Cracking
- Applications: Ceramic PCB



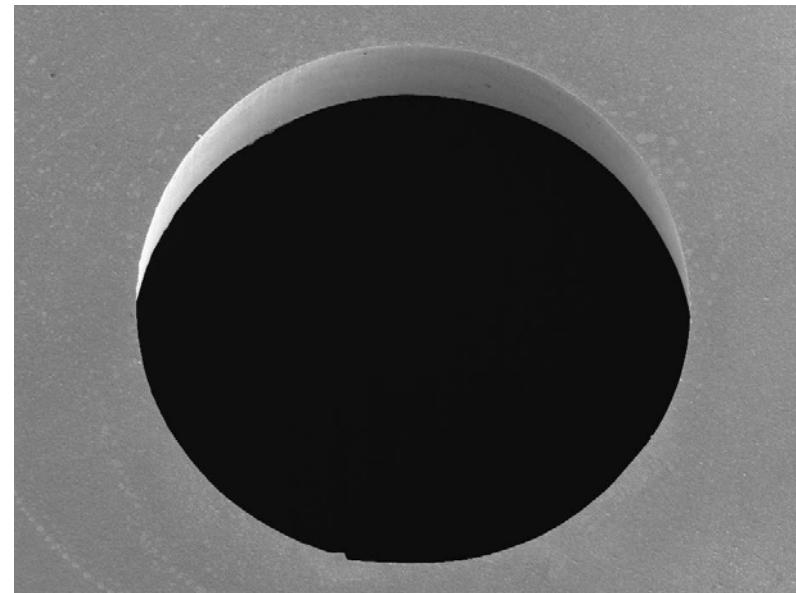


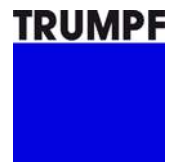


## Drilling with low Aspect Ratio

### Drilling of Silicon

- Percussion Drilling / Trepanning with Scanner Optics
- Diameter <math>< 100 \mu\text{m}</math> – X mm
- Low HAZ
- High edge quality
- Application: Through Silicon Vias for 3D packaging





# Cutting

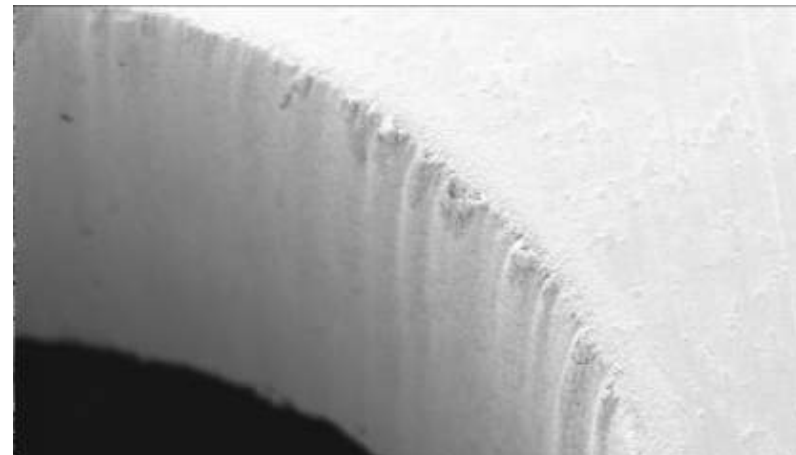




## Cutting with picosecond pulses

### Cutting of Nitinol

- Small cutting kerf ( $< 10\text{-}20\ \mu\text{m}$ )
- Negligible HAZ
- High quality of cutting edge
- No electro polishing!
- High yield
- High productivity due to high average power
- Application: Cutting of Stents, endoscopes

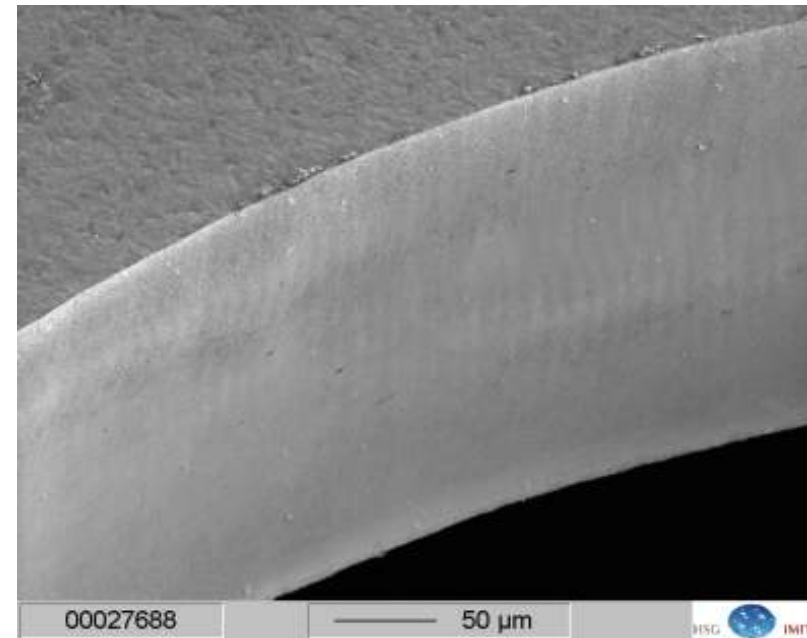




## Cutting with picosecond pulses

### Cutting of Silicon Wafers

- Small cutting kerf ( $< 20 \mu\text{m}$ )
- Negligible HAZ
- High quality of cutting edge
- High productivity due to high average power
- Applications: Waferdicing

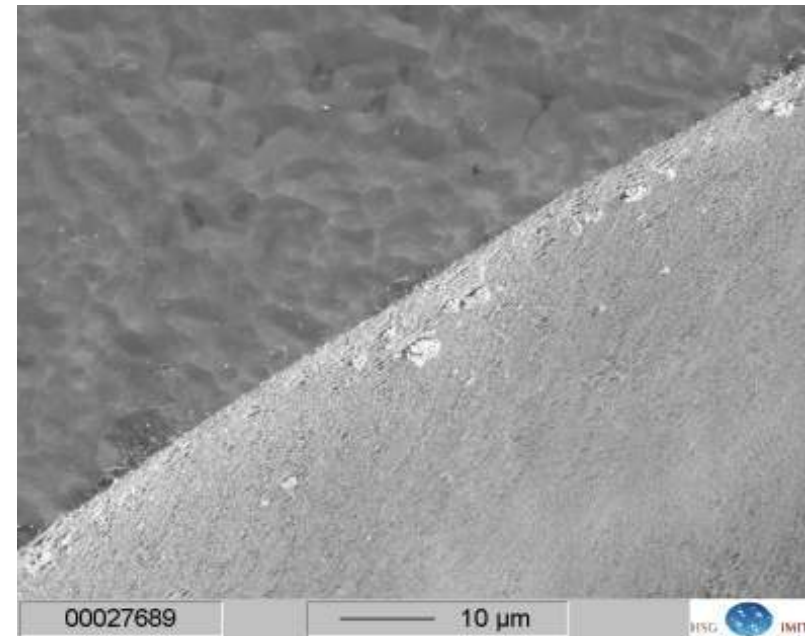




## Cutting with picosecond pulses

### Cutting of Silicon Wafers

- Small cutting kerf ( $< 20 \mu\text{m}$ )
- Negligible HAZ
- High quality of cutting edge
- High productivity due to high average power
- Applications: Waferdicing



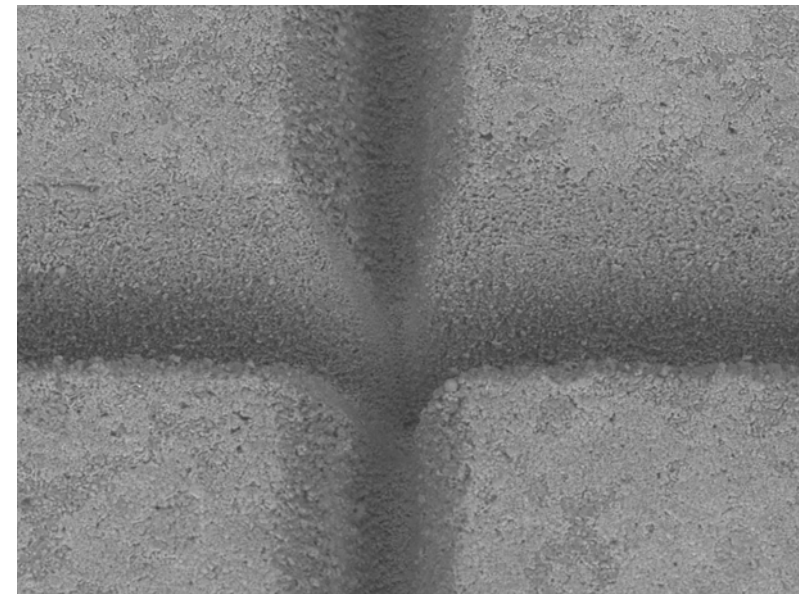




## Cutting with picosecond pulses

Scribing and cutting of Ceramics

- Small kerf width ( $< 20 \mu\text{m}$ )
- Negligible HAZ
- High quality of cutting edge
- High productivity due to high average power
- Applications: Scribing / cutting of ceramic PCBs



TRUMPF

2009/03/06

x800 100  $\mu\text{m}$

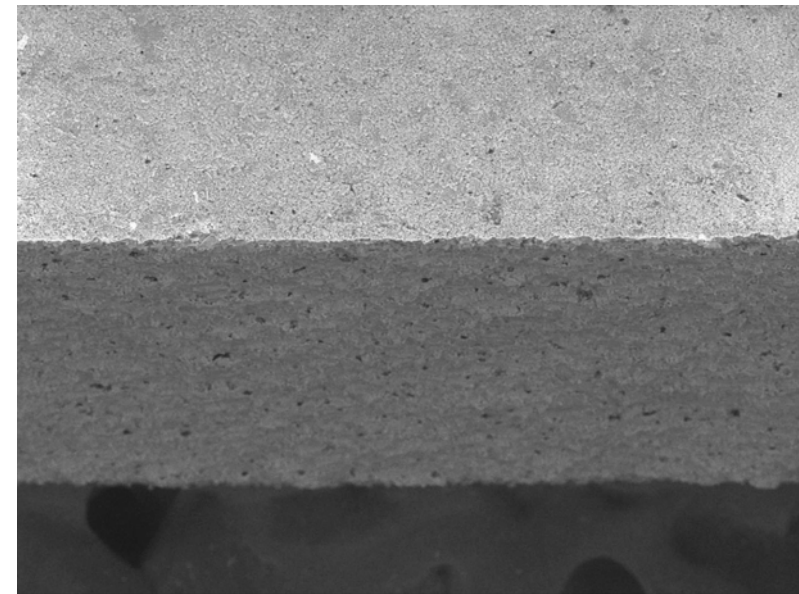




## Cutting with picosecond pulses

Scribing and cutting of Ceramics

- Small kerf width ( $< 20 \mu\text{m}$ )
- Negligible HAZ
- High quality of cutting edge
- High productivity due to high average power
- Applications: Scribing / cutting of ceramic PCBs



TRUMPF

2009/03/06

x600 100  $\mu\text{m}$

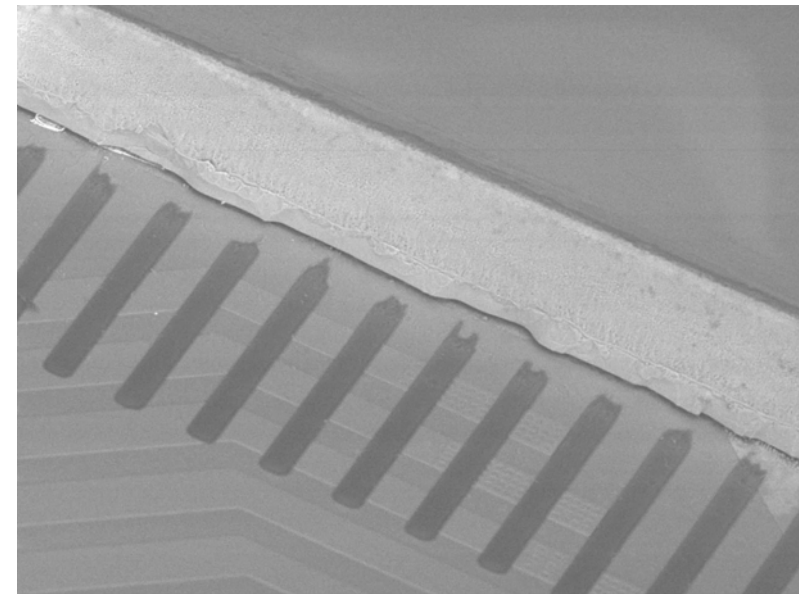




## Cutting with picosecond pulses

Scribing and cutting of thin glass

- Small kerf width ( $< 20 \mu\text{m}$ )
- Negligible HAZ
- High quality of cutting edge
- High productivity due to high average power
- Application: Scribing/cutting of thin glass for Flat-Panel-Displays



TRUMPF\_0038

2009.02.09

x400 200 um





# Thin Film Ablation with picosecond pulses

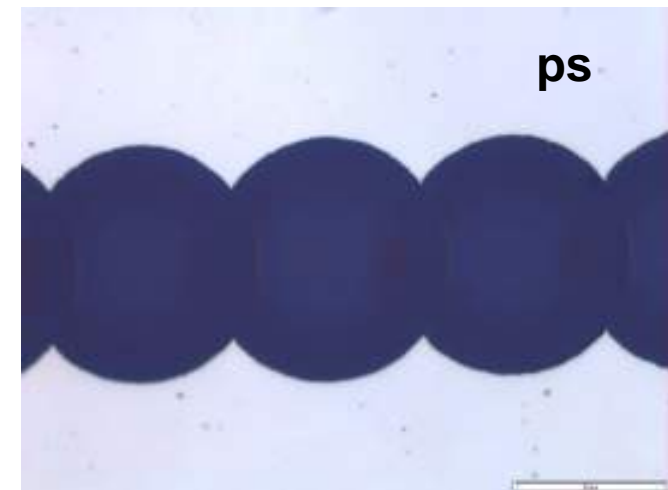
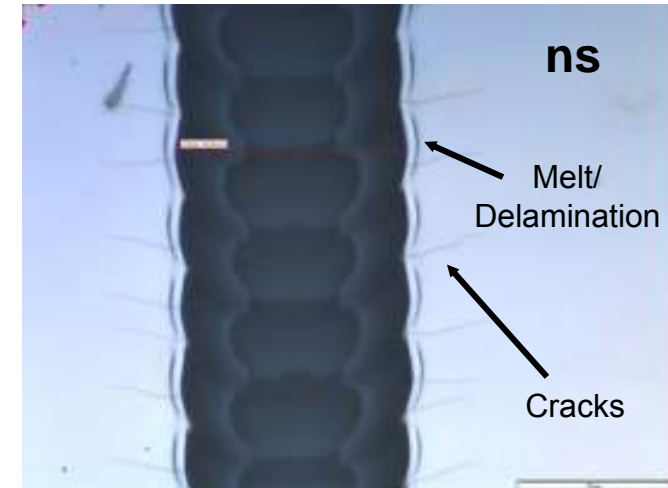




## Thin Film Ablation

Laser patterning of thin Mo on glass

- Burr free
- Melt free
- No delamination
- Isolated channel
- Application: P1 step for CIGS cell connection





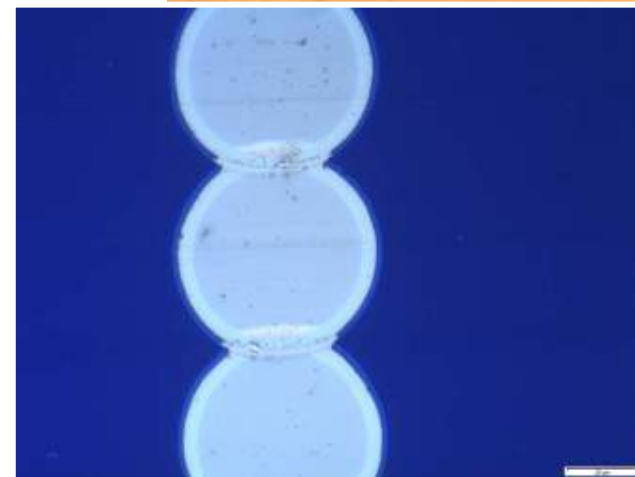
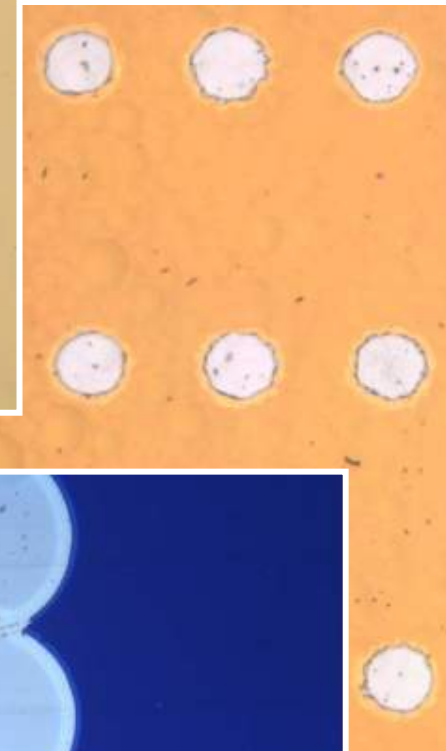
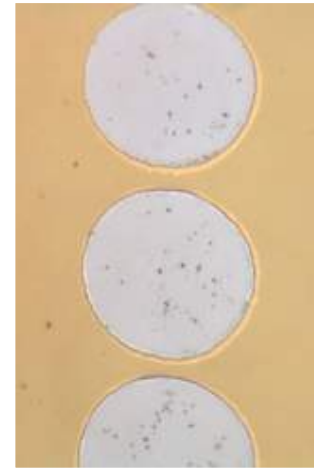


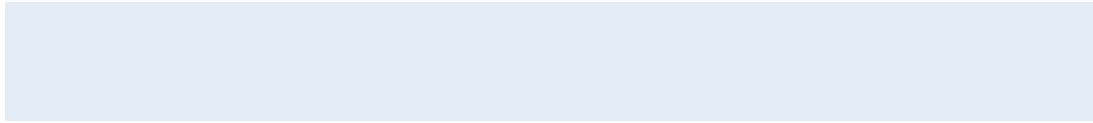
## Thin Film Ablation

Laser patterning of thin films on Silicon

Direct patterning of SiO/SiN layers

- Thickness of layers: 100 nm
- Single shot ablation
- Selective removal without affecting base material (Silicon)
- Application: Cell connection for Silicon Solar Cells, low-k dielectric grooving





# General Demands for Industrial Lasers





## General Demands for Industrial Lasers

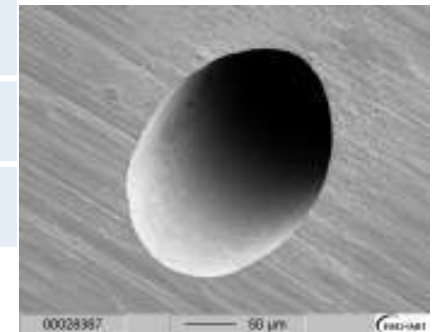
- High productivity





## TruMicro Series 5000

	TruMicro 5050	TruMicro 5250	TruMicro 5350
Average Power	50 W	25 W	> 15 W
Wavelength	1030 nm	515 nm	343 nm
Pulse Duration	< 10 ps	< 10 ps	< 10 ps
Max. Pulse Energy	250 μJ	125 μJ	> 75 μJ
Repetition Rate*	200/400 kHz	200/400 kHz	200/400 kHz
Beam Quality	$M^2 < 1.3$	$M^2 < 1.3$	$M^2 < 1.3$



\* Higher Repetition Rates upon request





## General Demands for Industrial Lasers

- High productivity AND high duty cycle







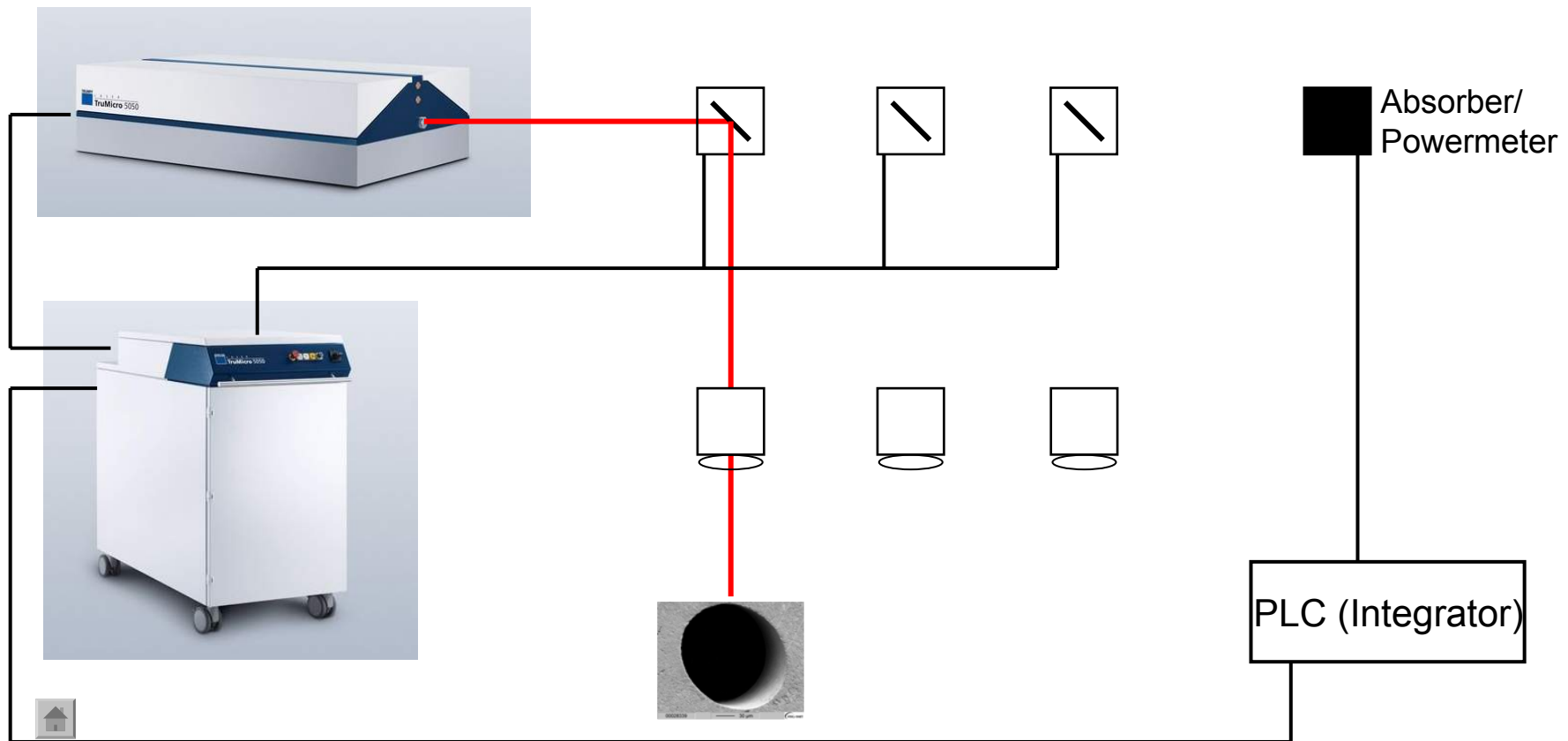
## External Multiplexing

- External beam switches for multiplexing
  - Up to 4 beam switches incl. safety circuit
  - Easy integration in TruControl
  - Maximise Laser-on Time
- Maximise Productivity



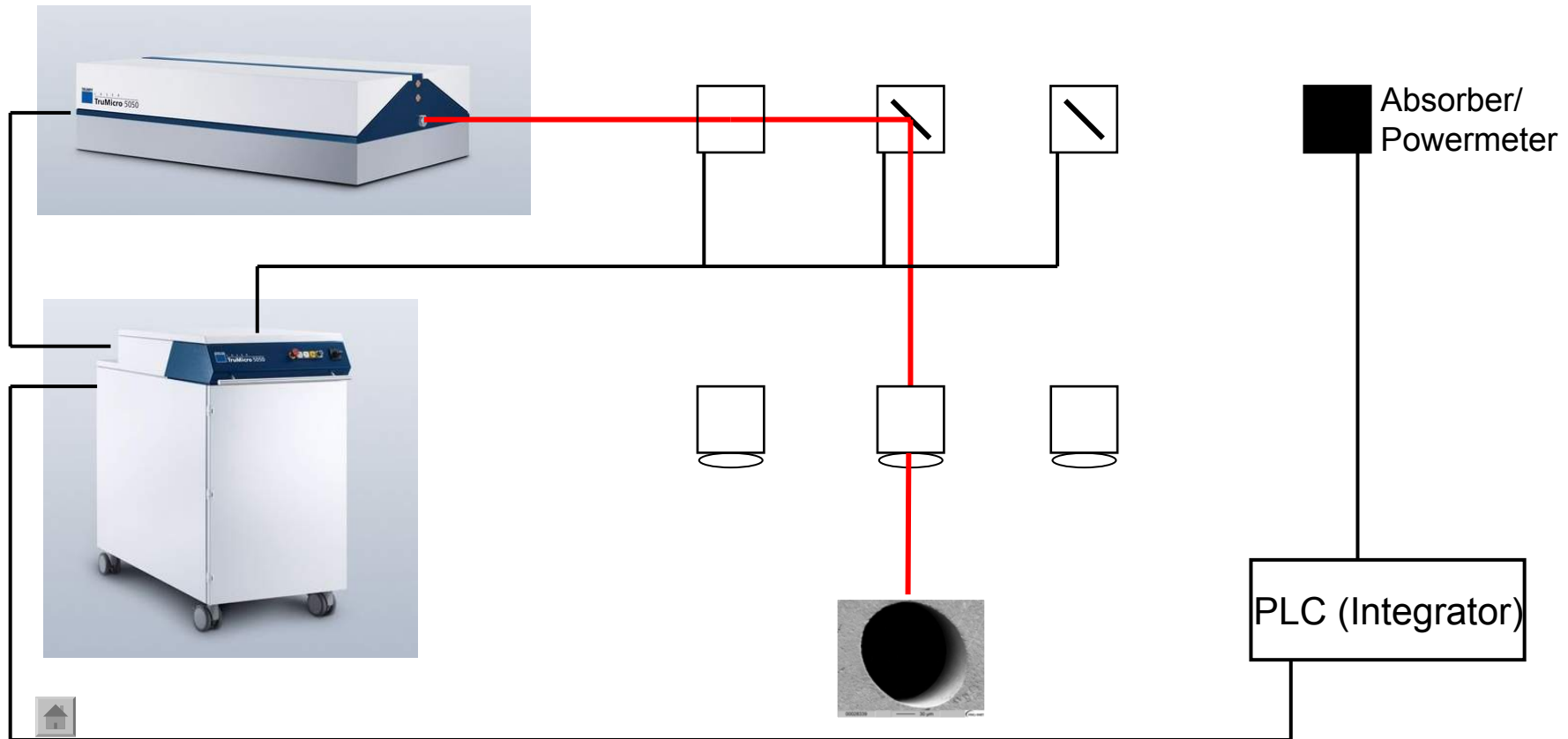


# Machine concept for external multiplexing



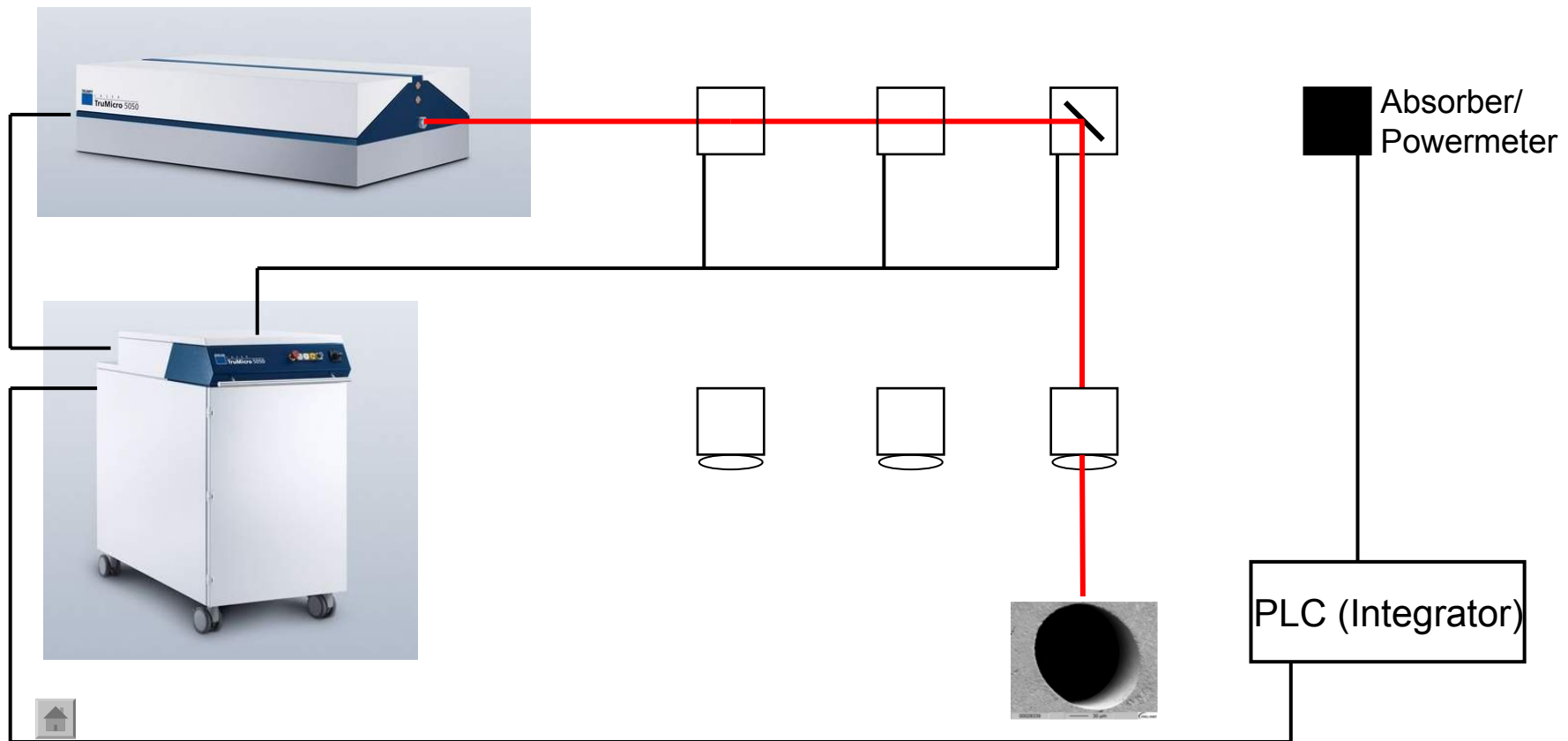


# Machine concept for external multiplexing



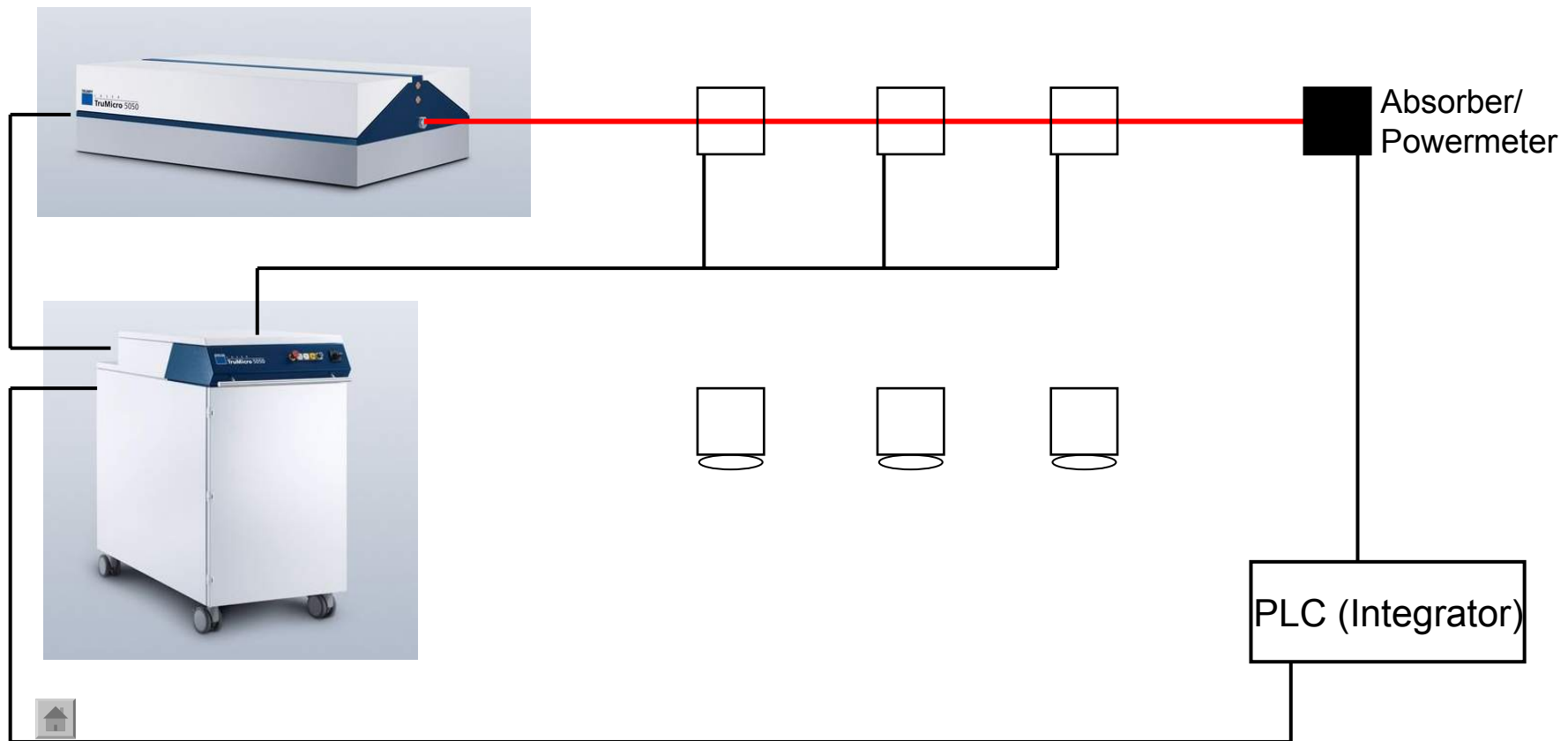


## Machine concept for external multiplexing





## Machine concept for external multiplexing







## General Demands for Industrial Lasers

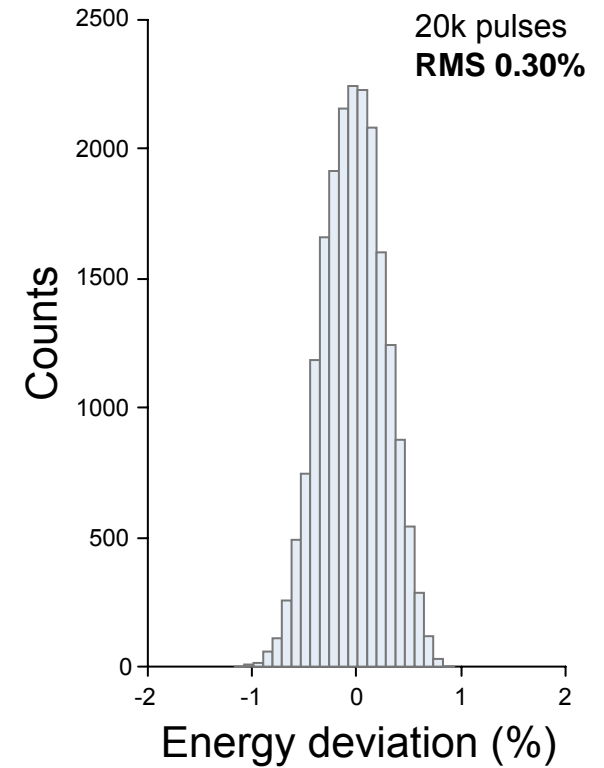
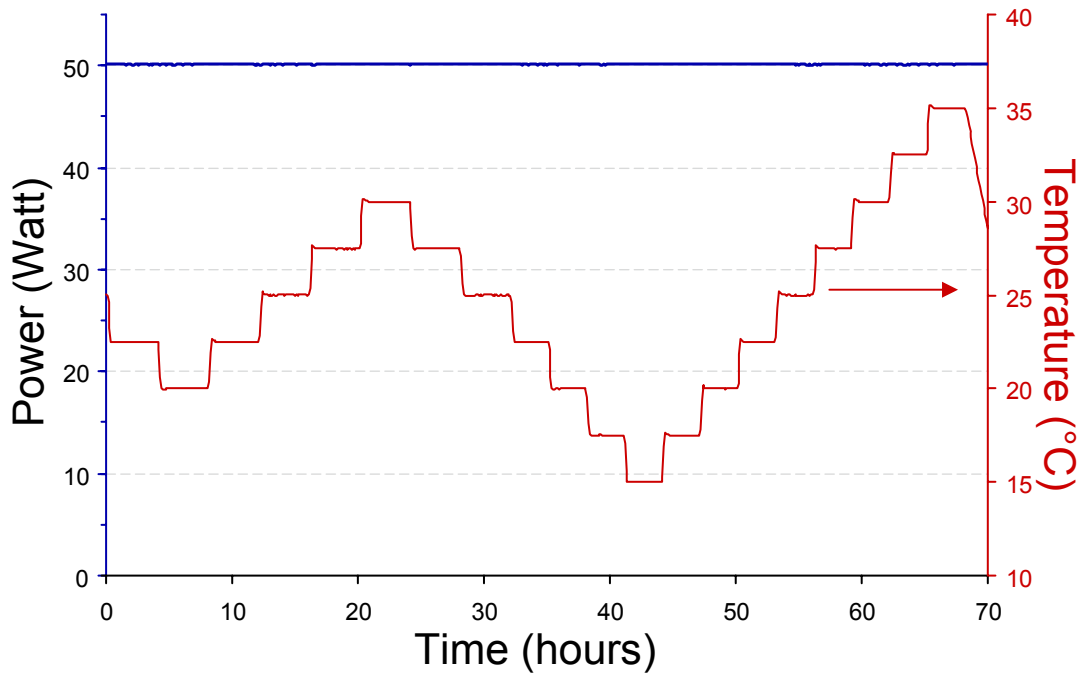
- High productivity, high duty cycle, high stability





# TruMicro 5050 - Stability

- Guaranteed Power stability < 1,5% for ambient temperatures of 20 – 30 °C
- Guaranteed Energy Stability: < 2% (RMS)





## General Demands for Industrial Lasers

- High productivity, high duty cycle, high stability
- High availability (> 98 % @ 24/7)
- Worldwide service and support 24/7 (Telepresence)





## TelePresence Portal – Facts & Figures

- Almost 100% of the devices are supplied with integrated modem and give the ability to TelePresence
- For 70 - 80% of the delivered devices our customers make use of TelePresence
- > 90% of all incoming inquiries can be solved without on-site action
- 80% of the cases are diagnosed within 15 minutes
- Only about 50% of the cases are defects – the other 50% are operation-, activation- and integration problems or system calibration
- TRUMPF has so far the only remote maintenance solution certified by the Federal Office for Safety in the Information Technology (BSI)!





## General Demands for Industrial Lasers

- High productivity, high stability
- High Availability (> 98 %)
- Worldwide service and support 24/7 (Telepresence)
- Long Service Intervals (> 5000 h)
- Long Lifetime of Pump Diode (> 20000 h)
- Low Total Cost of Ownership (< 10 Euro/hour)
- Process development and optimization in-house and on customer site





## Summary

For industrial picosecond lasers a only combination of

- Short pulses ( $< 10$  ps)
- High average power ( $> 50$  W)
- High pulse energy ( $> 150 - 250$   $\mu$ J)
- High (but not too high for scanner speeds) pulse frequency (200 - 400 kHz)

while GUARANTEEING

- Best beam quality ( $M^2 < 1,3$ )
- High beam roundness ( $> 90$  %)
- High pulse to pulse stability ( $< 2$  %)
- High availability ( $> 98$  %) and low TCO

enables for efficient and cost-effective micro machining!





**TRUMPF**



**Thank you!**

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78713 Schramberg  
[Sascha.Weiler@de.trumpf.com](mailto:Sascha.Weiler@de.trumpf.com)